REMARKS/ARGUMENTS

Reconsideration and withdrawal of the outstanding grounds of objection and rejection are respectfully requested in light of the above amendments and the remarks that follow.

The Examiner has objected to originally filed claim 1 as being in improper format and as failing to comply with 35 U.S.C. § 112, second paragraph. By this Amendment, claim 1 has been canceled in favor of newly submitted claims 2-9, claims 2 and 4 of which are presented in independent form. The newly presented claim contains none of the informalities identified by the Examiner in the Official Action.

The Examiner also rejected claim 1 under 35 U.S.C. § 102(e) as anticipated by U.S. Published Application 2002/0016396A1 to Wong et al. According to the Examiner, the reference discloses a capacitor having a physical effect through which electro-energy can be stored in resonance-excited, very small crystalline chemically dipolar particles or layers, thereby becoming conductive, and which are separated by an electrically insulating media.

Wong et al. disclose polymer-ceramic composites having high dielectric constants that are formed using polymers containing a metal acetylacetonate curing catalyst. The composites are said to be suitable for use in forming capacitors.

It is respectfully submitted, however, that Wong neither discloses nor even remotely suggests the specific process steps now contained in independent claims 2 and 4. For example, independent claim 2 requires applying a mixture of fluid resin and nano-particles onto a compound film (an isolated metallic foil) by means of electrostatic spraying in order to obtain a coated film, whereby the metallic foil acts as a counter electrode, the electro static spraying generating an electrical field; followed by the step of forming geometrically exact layers and field aligning the nano-particles by means of surface forces generated by the electrical field in combination with the capacitor effects. Nowhere in Wong et al. is this process disclosed.

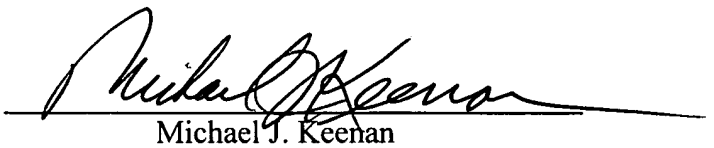
The reference also fails to disclose or suggest the process steps contained in independent claim 4 calling for alternately depositing a layer of nanoparticles and a layer of resin onto a carrier surface by means of chemical or physical vapor deposition in order to obtain a sandwich structure annealing the sandwich structure at a temperature of above 800° centigrade to achieve a Rutile type crystal phase, and then cooling the sandwich structure. Here again, the process is not found in Wong et al.

Dependent claims 3 and 5-9 contain additional limitations that are not found in the reference.

It is respectfully submitted that new claims 2-9 are now in condition for immediate allowance and early passage to issue is requested. In the event, however, any small matters remain outstanding, the Examiner is encouraged to telephone the undersigned so that the prosecution of this application can be expeditiously concluded.

Respectfully submitted,

NIXON & VANDERHYE P.C.

By: 

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